

Developer

Hoechst 4 ... 88%

Photoresist Developer()

Developer 92 2500 (600) 가 300

12.0% 2200 88.0%

150 300

TOKA가 1300 52% Shipley

900 , 36%

Nagase

Dan Industry 49%

Developer Photoresist TMAH(Tetra Metyl Ammonium Hyd-roxide)가

Developer (:MT/ ,%)			
	150	6.0	Hoechst A.G (80%)
	150	6.0	Dan Industry (49%)
TOKA	1300	52.0	
Shipley	900	36.0	
	2500	100.0	-

가 Photoresist 300 5000

Developer, Stripper, 1000

Developer 가

Developer 가 가

가

Photoresist Developer